Resonant network antennas for plasma applications in industry

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Radio-frequency resonant network antennas have recently attracted a wide interest as plasma sources and diagnostics. I will review the working principles and the applications of four novel resonant network antennas developed at the Swiss Plasma Center in Lausanne, Switzerland: 1) a planar large area source [1] (1.2x1.2 m²) for the industrial production of solar cells, packaging, and surface treatment; 2) a cylindrical birdcage antenna [2] for helicon wave generation for negative ion production; 3) a high-pressure antenna for food and powder treatment in fluidized bed reactor processes; 4) a miniaturized (cm-size) inductive probe for plasma conductivity measurement [3] for process control and characterization.

- [1] Ph. Guittienne, R. Jacquier, A. A. Howling, I. Furno, *Plasma Sources Sci. Technol.* **26**, 035010 (2017).
- [2] I. Furno et al., *EPJ Web of Conferences* **157**, 03014 (2017).
- [3] Patent: "Method and Device for Determining Plasma Characteristics", 4 May 2015 EP15166251.7

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